

PATENT ABSTRACTS OF JAPAN

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(71)Applicant : ASAHI GLASS CO LTD

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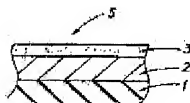
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(54) IMPROVED PHOTOMASK BLANK AND PHOTOMASK

(57)Abstract:

PURPOSE: To prevent overhang due to etching to the utmost by forming a Cr light shading layer and a reflection inhibiting layer contg. a specified amt. of N on a transparent plate to form a photomask blank.

CONSTITUTION: The photomask 5 high in pattern precision can be prepared by forming the light shading layer 2 contg. Cr or Cr oxide in a proper amt., and capable of improving acid resistance or etching speed, when needed, and the reflection inhibiting layer 3 made of chromium nitride oxide contg. in an amt. of $\geq 25\text{mol}\%$ N, especially, 25W35% in order to reduce overhang to the utmost, and to maintain reflectance low, in succession on a transparent support 1 made of borosilicate glass smooth and flat in the surface, low expansive glass, e.g., aluminosilicate glass, soda.lime glass, quartz glass, or sapphire.



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